

Korean International Semiconductor Conference & Exhibition on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[TuE2] CMP Consumables: Conditioning,	, Monitoring, and Abrasives
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Session Date November 11 (Tue.), 2025

Session Time 14:50-16:30

Session Room Room E (Sicily Room, 1F)

[TuE2-1] [Invited] 14:50-15:20

CMP Pad Conditioning of the Future: Fundamentals, Emerging Technologies, and Development Pathways

Yongsik Moon, Kyoung-Kuk Kwack, Joohan Lee, Jongkuk Park, Eunhwa Song, Youngtae Jeon, Juhee Lee, Sungyu Park, Yujeong Jin, and Jongjae Lee (EHWA Diamond, Korea)

[TuE2-2] [Invited] 15:20-15:50

Slurry Sensing for CMP Processes

Jin Su Hong, Min Cheol Kim, and Min Ku Kim (Hanyang Univ., Korea)

[TuE2-3] 15:50-16:10

Synthesis Strategies of Ceria Abrasives for Optimizing Dielectric Chemical Mechanical Planarization Performance

Jae Uk Hur and Jeong Ho Lee (Soulbrain Co., Ltd., Korea)

[TuE2-4] 16:10-16:30

Fenton Reaction Enhancing Significant Chemical Oxidation for Ag Chemical Mechanical Planarization

Man-Hyup Han, Hyun-Sung Koh, Il-Haeng Heo, Min-Ji Kim, Woo-Hyun Jin, Jin-Woo Kim, Seung-Hwan Kim, Jin-Sub Park, and Jea-Gun Park (Hanyang Univ., Korea)